

Request for Reconsideration  
U.S. Patent Application Ser. No.: 10/084,204

Applicants respectfully submit that the present claims are clear and definite as written and that they particularly point out and distinctly claim the subject matter which Applicants regard as the invention. Applicants also respectfully submit that the present specification provides a fully enabling disclosure for the invention, as claimed, and that the disclosure would enable one of ordinary skill in the art to make and use the invention, as claimed. Applicants request that the Examiner reconsider and withdraw the rejection under 35 U.S.C. §112, second paragraph, in view of the following remarks.

An object of the present invention is to provide a positive photoresist composition which can form a resist pattern of not more than half a micron having a good shape in which dimensional changes over a wide range of the surface of a substrate are minimized, and to provide, in a resist pattern forming process using a large-diameter substrate, a process for forming a resist pattern using the composition. Applicants respectfully submit that the objects of the present invention can be achieved even if quinonediazide methyl gallate is not used in the composition. In the examples of the present specification, quinonediazide methyl gallate is used as one kind of preferred component, but quinonediazide methyl gallate is not an indispensable component.

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Applicants' invention is not limited to the examples or the preferred components. The Examiner has not provided any evidence that one of ordinary skill in the art could not make or use Applicants' invention as claimed.

For the above reasons, it is respectfully submitted that Applicants' claims are clear and definite and it is requested that the rejection under 35 U.S.C. §112 be reconsidered and withdrawn.

**III. The Rejection Under 35 U.S.C. § 103**

Claims 1-4 and 6-20 are rejected under 35 U.S.C. § 103 as allegedly being obvious over Kawata in view of Momota, Sato, Ando and Uetani.

Specifically, the Examiner stated that it would be obvious to one of ordinary skill in the art to use an alkyl substituted polyphenol photosensitive compound disclosed in Momota in the photoresist composition of Kawata in place of (B-7) as a photosensitive ingredient with the reasonable expectation of same or similar results as disclosed in Kawata for excellent sensitivity, resolution and film thickness loss.

Applicants respectfully submit that the present invention is not obvious over the disclosures of Kawata, Momota, Sato, Ando and Uetani and request that the Examiner reconsider and withdraw this rejection in view of the following remarks.

Even if it is known that the phenol compounds as disclosed in Sato, Ando and Uetani provide some improved sensitivity and pattern formation, the combination of the phenol compounds with the photosensitizer as claimed in the present is still not

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obvious to one of ordinary skill in the art. The combination of the phenol compounds with the photosensitizer as claimed provides an unexpected and superior results over that expected from the cited art. That is, the use of the claimed phenol compounds with the claimed photosensitizer unexpectedly provides a positive photoresist composition which can form a resist pattern of not more than half a micron having a good shape in which dimensional changes over a wide range of the surface of a large-diameter substrate are minimized.

The unexpected superiority is clearly seen from the comparison between Example 1 and Comparative Examples 1 and 2. Particularly, Comparative Example 2, which uses the claimed type of photosensitizes and does not use the claimed type of phenol compound of the present invention, provides poor dimensional change rate, 21.43%. This is compared with Example 1, which achieves a value of 10.86%. See Table 3 of Applicants' specification.

As seen from the above, the object of the present invention cannot be achieved when the specific phenol compound is not used. Further, although Comparative Example 1 provides good sensitivity, definition and focal depth range properties, poor dimensional change rate is obtained. Therefore, only when the claimed phenol compound is used, the desired effects are not obtained.

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The references cited do not suggest the combination of the present invention. Furthermore, Applicants' claimed invention provides unexpected and superior results over that of the cited art.

For the above reasons, it is respectfully submitted that the subject matter of claims 1-4 and 6-20 is neither taught by nor made obvious from the disclosures of Kawata, Momota, Sato, Ando and Uetani and it is requested that the rejection under 35 U.S.C. §103(a) be reconsidered and withdrawn.

**IV. Conclusion**

In view of the above, Applicants respectfully submit that their claimed invention is allowable and ask that the rejection under 35 U.S.C. §112 and the rejection under 35 U.S.C. §103 be reconsidered and withdrawn. Applicants respectfully submit that this case is in condition for allowance and allowance is respectfully solicited.

If any points remain at issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the local exchange number listed below.

Applicants hereby petition for any extension of time which may be required to maintain the pendency of this case. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880.

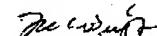
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Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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